Non-Final Amendment filed on May 27, 2008

Page 2 of 17

Amendments to the Claims:

This listing of claims will replace all prior versions and listings of claims in the application.

Listing of Claims:

- 1. (Currently Amended) A radiation-sensitive resin composition comprising:
- (A) a resin which comprises from 5 to 90 mole percent of a recurring unit (1-1) shown by the following formula (I-1):

$$\begin{array}{c} + \text{CH}_2 - \text{C}_{12}^{\text{Ta}} \\ & \times \\ & \times$$

wherein R_{1a} represents a hydrogen atom, a methyl group, a hydroxyalkyl group having 1-4 carbon atoms, or a perfluoroalkyl group having 1-4 carbon atoms, X_1 and X_2 individually represent a hydrogen atom, a fluorine atom, an alkyl group having 1-4 carbon atoms, or a fluoroalkyl group having 1-4 carbon atoms, 1 is an integer of 0-5, and n is an integer of 0-2, the resin being insoluble or scarcely soluble in alkali, but becoming alkali soluble by the action of an acid, and

(B) a photoacid generator, wherein the resin does not comprise an aromatic ring.

Non-Final Amendment filed on May 27, 2008

Page 3 of 17

2. (Currently Amended) A radiation-sensitive resin composition comprising:

(A) a resin which comprises a recurring unit (1-1) shown by the following formula (I-1):

wherein R_{1a} represents a hydrogen atom, a methyl group, a hydroxyalkyl group having 1-4 carbon atoms, or a perfluoroalkyl group having 1-4 carbon atoms, X_1 and X_2 individually represent a hydrogen atom, a fluorine atom, an alkyl group having 1-4 carbon atoms, or a fluoroalkyl group having 1-4 carbon atoms, 1 is an integer of 0-5, and n is an integer of 0-2, and a recurring unit (1-2) shown by the following formula (I-2):

Non-Final Amendment filed on May 27, 2008

Page 4 of 17

wherein R_{1b} represents a hydrogen atom or a methyl group, R_{1c} individually represents a monovalent alicyclic hydrocarbon group having 4-20 carbon atoms or a derivative thereof, or a linear or branched alkyl group having 1-4 carbon atoms, provided that (1) at least one of the R_{1c} groups is a monovalent alicyclic hydrocarbon group having 4-20 carbon atoms, or (2) any two of the R_{1c} groups form, in combination and together with the carbon atom with which these groups bond, a divalent alicyclic hydrocarbon group having 4-20 carbon atoms or a derivative thereof, with the other R_{1c} group being a monovalent alicyclic hydrocarbon group having 4-20 carbon atoms or a derivative thereof, or a linear or branched alkyl group having 1-4 carbon atoms the resin being insoluble or scarcely soluble in alkali, but becoming alkali soluble by the action of an acid, and

- (B) a photoacid generator,
- wherein the resin does not comprise an aromatic ring.
- 3. (Original) The radiation sensitive resin composition according to claim 2, wherein the group $-C(R_{1c})_3$ in the formula (I-2) is a l-alkyl-1-cycloalkyl group, 2-alkyl-2-adamantyl group, (1-alkyl-1-adamantyl)alkyl group, or (1-alkyl-1-norbornyl)alkyl group.
- 4. (Original) The radiation-sensitive resin composition according to claim 1, wherein the resin does not contain a lactone ring.
 - 5. (Currently Amended) A radiation-sensitive resin composition comprising:
- (A) a resin which comprises from 5 to 90 mole percent of a recurring unit (1-1) shown by the following formula (I-1):

Non-Final Amendment filed on May 27, 2008

Page 5 of 17

$$+CH_2-R_3$$
 $(I-1)$
 X_1
 X_2
 X_3
 X_4
 X_2
 X_3
 X_4
 X_5
 X_7
 X_7
 X_7
 X_8
 X_8
 X_8
 X_9
 $X_$

wherein R_{1a} represents a hydrogen atom, a methyl group, a hydroxyalkyl group having 1-4 carbon atoms, or a perfluoroalkyl group having 1-4 carbon atoms, X_1 and X_2 individually represent a hydrogen atom, a fluorine atom, an alkyl group having 1-4 carbon atoms, or a fluoroalkyl group having 1-4 carbon atoms, 1 is an integer of 0-5, and n is an integer of 0-2, the resin being insoluble or scarcely soluble in alkali, but becoming alkali soluble by the action of an acid, and

(B) a photoacid generator,

wherein the resin does not contain a lactone ring,

wherein the resin does not comprise an aromatic ring, and

wherein the content of the recurring unit (1-1) in the resin is 40-90 mol% in 100 mol% of the total recurring units forming the resin.

- 6. (Currently Amended) A radiation-sensitive resin composition comprising:
- (A) a resin which comprises a recurring unit (1-1) shown by the following formula (I-1):

Non-Final Amendment filed on May 27, 2008

Page 6 of 17

$$\begin{array}{c} \begin{array}{c} \begin{array}{c} \begin{array}{c} \begin{array}{c} \begin{array}{c} \begin{array}{c} \\ \end{array}\\ \end{array}\\ \end{array}\\ \begin{array}{c} \end{array}\\ \end{array}\\ \begin{array}{c} \begin{array}{c} \\ \end{array}\\ \end{array}\\ \begin{array}{c} \end{array}\\ \end{array}\\ \begin{array}{c} \end{array}\\ \begin{array}{c} \\ \end{array}\\ \end{array}\\ \begin{array}{c} \end{array}\\ \begin{array}{c} \\ \end{array}\\ \begin{array}{c} \\ \end{array}\\ \end{array}\\ \begin{array}{c} \begin{array}{c} \\ \end{array}\\ \end{array}\\ \begin{array}{c} \\ \end{array}\\ \begin{array}{c} \\ \end{array}\\ \end{array}$$

wherein R_{1a} represents a hydrogen atom, a methyl group, a hydroxyalkyl group having 1-4 carbon atoms, or a perfluoroalkyl group having 1-4 carbon atoms, X_1 and X_2 individually represent a hydrogen atom, a fluorine atom, an alkyl group having 1-4 carbon atoms, or a fluoroalkyl group having 1-4 carbon atoms, 1 is an integer of 0-5, and n is an integer of 0-2, and a recurring unit (1-3) shown by the following formula (I-3):

$$+CH_2$$
 $+CH_2$
 $+CH_3$
 $+CH_$

wherein R_{1b} represents a hydrogen atom or a methyl group, the resin being insoluble or scarcely soluble in alkali, but becoming alkali soluble by the action of an acid, and

(B) a photoacid generator,

Non-Final Amendment filed on May 27, 2008

Page 7 of 17

wherein the resin does not comprise an aromatic ring.

- 7. (Original) The radiation-sensitive resin composition according to claim 6, wherein the content of the recurring unit (1-1) in the resin is 5-25 mol% in 100 mol% of the total recurring units forming the resin.
 - 8. (Currently Amended) A radiation-sensitive resin composition comprising:
- (A) a resin which comprises a recurring unit (1-1) shown by the following formula (I-1):

wherein R_{1a} represents a hydrogen atom, a methyl group, a hydroxyalkyl group having 1-4 carbon atoms, or a perfluoroalkyl group having 1-4 carbon atoms, X_1 and X_2 individually represent a hydrogen atom, a fluorine atom, an alkyl group having 1-4 carbon atoms, or a fluoroalkyl group having 1-4 carbon atoms, 1 is an integer of 0-5, and n is an integer of 0-2, and a recurring unit (1-4) shown by the following formula (I-4):

Non-Final Amendment filed on May 27, 2008

Page 8 of 17

wherein R_{1b} represents a hydrogen atom or a methyl group, A represents a linear or branched alkyl or alkylene group having 1-4 carbon atoms or a monovalent or divalent alicyclic hydrocarbon group having 4-20 carbon atoms or a derivative thereof, and n is an integer of 0-2, the resin being insoluble or scarcely soluble in alkali, but becoming alkali soluble by the action of an acid, and

- (B) a photoacid generator, wherein the resin does not comprise an aromatic ring.
- 9. (Original) The radiation-sensitive resin composition according to claim 1, further comprising (C) an acid diffusion controller.
 - 10. (Currently Amended) A radiation-sensitive resin composition comprising:
- (A) a resin which comprises a recurring unit (1-1) shown by the following formula (I-1):

Non-Final Amendment filed on May 27, 2008

Page 9 of 17

$$+CH_2-R_3$$
 $(I-1)$
 X_1
 X_2
 X_3
 X_4
 X_2
 X_3
 X_4
 X_5
 X_7
 X_7
 X_7
 X_8
 X_8
 X_8
 X_9
 $X_$

wherein R_{1a} represents a hydrogen atom, a methyl group, a hydroxyalkyl group having 1-4 carbon atoms, or a perfluoroalkyl group having 1-4 carbon atoms, X_1 and X_2 individually represent a hydrogen atom, a fluorine atom, an alkyl group having 1-4 carbon atoms, or a fluoroalkyl group having 1-4 carbon atoms, 1 is an integer of 0-5, and n is an integer of 0-2, the resin being insoluble or scarcely soluble in alkali, but becoming alkali soluble by the action of an acid,

- (B) a photoacid generator, and
- (C) an acid diffusion controller.

wherein the resin does not comprise an aromatic ring.

- 11. (Currently Amended) A radiation-sensitive resin composition comprising:
- (A) a resin which comprises a recurring unit (1-1) shown by the following formula (I-1):

Non-Final Amendment filed on May 27, 2008

Page 10 of 17

wherein R_{1a} represents a hydrogen atom, a methyl group, a hydroxyalkyl group having 1-4 carbon atoms, or a perfluoroalkyl group having 1-4 carbon atoms, X_1 and X_2 individually represent a hydrogen atom, a fluorine atom, an alkyl group having 1-4 carbon atoms, or a fluoroalkyl group having 1-4 carbon atoms, 1 is an integer of 0-5, and n is 1 or 2, the resin being insoluble or scarcely soluble in alkali, but becoming alkali soluble by the action of an acid, and

- (B) a photoacid generator, wherein the resin does not comprise an aromatic ring.
- 12. (Previously Presented) The radiation-sensitive resin composition according to Claim 11, wherein n is 1, 1 is 1, each X_1 is H and each X_2 is CF_3 .
 - 13. (New) A radiation-sensitive resin composition comprising:
- (A) a copolymer resin which comprises a recurring unit (1-1) shown by the following formula (I-1) and one or more other recurring units:

Non-Final Amendment filed on May 27, 2008

Page 11 of 17

wherein R_{1a} represents a hydrogen atom, a methyl group, a hydroxyalkyl group having 1-4 carbon atoms, or a perfluoroalkyl group having 1-4 carbon atoms, X_1 and X_2 individually represent a hydrogen atom, a fluorine atom, an alkyl group having 1-4 carbon atoms, or a fluoroalkyl group having 1-4 carbon atoms, 1 is an integer of 0-5, and n is an integer of 0-2, the resin being insoluble or scarcely soluble in alkali, but becoming alkali soluble by the action of an acid, and

- (B) a photoacid generator.
- 14. (New) The radiation-sensitive resin composition of Claim 13, wherein the resin (A) comprises a recurring unit (1-2) shown by the following formula (I-2):

$$+CH_2$$
 $+CH_2$
 $+CH_$

Non-Final Amendment filed on May 27, 2008

Page 12 of 17

wherein R_{1b} represents a hydrogen atom or a methyl group, R_{1c} individually represents a monovalent alicyclic hydrocarbon group having 4-20 carbon atoms or a derivative thereof, or a linear or branched alkyl group having 1-4 carbon atoms, provided that (1) at least one of the R_{1c} groups is a monovalent alicyclic hydrocarbon group having 4-20 carbon atoms, or (2) any two of the R_{1c} groups form, in combination and together with the carbon atom with which these groups bond, a divalent alicyclic hydrocarbon group having 4-20 carbon atoms or a derivative thereof, with the other R_{1c} group being a monovalent alicyclic hydrocarbon group having 4-20 carbon atoms or a derivative thereof, or a linear or branched alkyl group having 1-4 carbon atoms.

- 15. (New) The radiation sensitive resin composition according to Claim 14, wherein the group $-C(R_{1c})_3$ in the formula (I-2) is an alkylcycloalkyl group.
- 16. (New) The radiation-sensitive resin composition of Claim 13, wherein the content of the recurring unit (1-1) in the resin is 10-80 mol% in 100 mol% of the total recurring units forming the resin.
- 17. (New) The radiation-sensitive resin composition of Claim 13, wherein the content of the recurring unit (1-1) in the resin is 10-50 mol% in 100 mol% of the total recurring units forming the resin.
- 18. (New) The radiation-sensitive resin composition of Claim 13, wherein the resin (A) comprises a recurring unit (1-3) shown by the following formula (I-3):

Non-Final Amendment filed on May 27, 2008

Page 13 of 17

wherein R_{1b} represents a hydrogen atom or a methyl group.

- 19. (New) The radiation-sensitive resin composition of Claim 13, further comprising (C) an acid diffusion controller.
- 20. (New) The radiation-sensitive resin composition according to Claim 13, wherein in formula (I-1) n is 1, 1 is 1, each X_1 is H and each X_2 is CF_3 .